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(54) Title: APPARATUS AND METHOD FOR IN-SITU CHEMICAL SEPARATION AND RECIRCULATION IN A CHEMICAL MECHANICAL PROCESSING SYSTEM

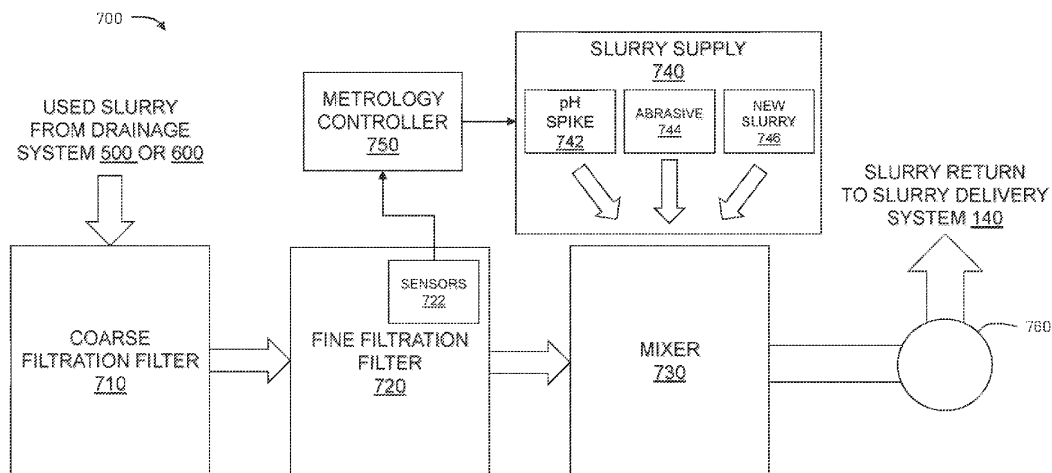


FIG. 7

(57) Abstract: An apparatus and method for in-situ chemical separation and recirculation in a chemical mechanical processing system are provided. In one aspect, a chemical mechanical planarization system includes a polishing platen having a surface configured to polish a substrate and a slurry delivery system configured to deliver slurry to the surface of the polishing platen. The apparatus can further include an effluent capture apparatus configured to capture the slurry from the polishing platen, filter the captured slurry, and provide the filtered slurry to the slurry delivery system.

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